

	Application No.	Applicant(s)
Notice of Allowability	10/642,969	CRENSHAW ET AL.
	Examiner	Art Unit
	David Nhu	2818
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to 7/18/05.	•	
2. The allowed claim(s) is/are 12-20.		
3. The drawings filed on 18 August 2003 are accepted by the Examiner.		
 4.		
Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-948) 3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. Interview Summary Paper No./Mail Da 8), 7. Examiner's Amendi 8. Examiner's Statem 9. Other	te

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REASONS FOR ALLOWANCE

1. Claims 12-20 are allowed.

2. The following is an examiner's statement of reasons for allowance: None of the references of record teaches or suggests as cited in claims 12: depositing a uniform layer of a metal material over said hard mask material, wherein said deposited layers form a stack; patterning and etching a said bottom electrode of said micro-electromechanical switch and resistor

lengths from said stack; etching said hard mask and metal material from said patterned

resistor length to form said RF switch.

3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons

for Allowance."

CONCLUSION

4. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure: Linn et al (5,547,896): Direct Etch for Thin Film Resistor Using a Hard Mask.

5. Any inquiry concerning this communication on earlier communications from the examiner should be directed to David Nhu, (571)272-1792. The examiner can normally be reached on Monday-Friday from 7:30 AM to 5:00 PM.

The examiner's supervisor, David Nelms can be reached on (571)272-1787.

The fax phone number for the organization where this application or proceeding is assigned is (703)872-9306.

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Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

David Nhu

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August 1st, 2005

DAVID